

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1898	SERIAL NO. 09/633,556
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Gurtej S. Sandhu et al.	
				FILING DATE August 7, 2000	GROUP 2813

U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>[Handwritten signatures and initials in left margin]</i>	AA	5,032,545	07/91	Doan et al.	—	—	
	AB	5,436,481	07/95	Egawa et al.	—	—	
	AC	5,378,645	01/95	Inoue et al.	—	—	
	AD	5,258,333	11/93	Shappir et al.	—	—	
	AE	5,518,946	05/96	Kuroda	—	—	
	AF	5,445,999	08/95	Thakur et al.	—	—	
	AG	5,382,533	01/95	Ahmad et al.	—	—	
	AH	5,663,077	09/97	Adachi et al.	—	—	
	AI	5,026,574	06/91	Economu et al.	—	—	
	AJ	5,026,574	06/91	Economu et al.	—	—	
	AK	5,612,558	11/95 3/1997	Harshfield	—	—	
	AL	5,719,083	06/95 2/1998	Komatsu	—	—	

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							Yes	No
	AM	WO 96/39713	12/96	PCT				
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	AO							
	AP							
	AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
AR		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 212-213.
AS		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 188-189, 194-195, 609-614.
AT		Ko, L. et al., "The Effect of Nitrogen Incorporation into the Gate Oxide By Using Shallow Implantation of Nitrogen and Drive-In Process", IEEE 1996, pp. 32-35.

EXAMINER <i>[Signature: Hanna Schults]</i>	DATE CONSIDERED 6/5/02
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
<i>Handwritten:</i> Gurtej Sandhu	AA	5,760,475	06/98	Cronin				
	AB	5,834,372	11/98	Lee				
	AC	5,619,057	04/96 1997	Komatsu				
	AD	5,633,036	05/97	Seebauer et al.				
	AE	6,054,396	04/00	Doan				
	AF	6,174,821	01/01	Doan				
	AG	5,939,750	08/99	Early				
	AH	5,254,489	10/93	Nakata				
	AI	5,464,792	11/95	Tseng et al.				
	AJ	5,620,908	04/97	Inoh et al.				
AK	5,716,864	02/98	Abe					
AL	5,972,783	10/99	Arai et al.					
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	AR		Doyle, B. et al., "Simultaneous Growth of Different Thickness Gate Oxides in Silicon CMOS Processing", IEEE Vol. 16 (7), July 1995, pp. 301-302.					
	AS		Kuroi, T. et al., "The Effects of Nitrogen Implantation Into P+Poly-Silicon Gate on Gate Oxide Properties", 1994 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1994, pp. 107-108.					
	AT		Liu, C.T. et al., "Multiple Gate Oxide Thickness for 2GHz System-on-a-Chip Technologies" IEEE 1998, pp. 589-592.					
EXAMINER <i>Handwritten:</i> Laura Schilling				DATE CONSIDERED <i>Handwritten:</i> 6/5/02				
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	AA	6,091,109	07/00	Hasegawa	—	—	
	AB	6,080,682	06/00	Ibok	—	—	
	AC	5,685,949	11/97	Yashima	—	—	
	AD	6,268,296 B1	07/01	Misium et al.	—	—	
	AE	6,232,244 B1	05/01	Ibok	—	—	
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	AL						

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Unknown 2813

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AC	6,228,701 B1	05/01	Dehm et al.			
AD	6,136,636	10/00	Wu			
AE	6,033,998	03/00	Aronowitz et al.			
AF	6,057,220	05/00	Ajmera et al.			
AG	6,087,229	07/00	Aronowitz et al.			
AH	5,998,253	12/99	Loh et al.			
AI	5,763,922	06/98	Chau			
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AK	5,960,289	09/99	Tsui et al.			
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